PRECURSOR MOLARITY EFFECT ON THE MEMRISTIVE BEHAVIOUR OF SPIN COATED TITANIA THIN FILM

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In the name of ALLAH S.W.T, the most Merciful and most Gracious

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ABSTRACT

This project is mainly about device fabrication which is titanium dioxide (TiO₂) memristor and characterized it for the electrical behaviour and physical characteristic. TiO₂ thin film is the active layer in between two different substrates which are the 60nm platinum (Pt) as the top electrode and ITO substrate as the bottom electrode in the vertical configuration. The TiO₂ thin film was deposited on the ITO substrate by sol-gel spin coating method. Prior to the deposition process, precursor molarity (Titanium (IV) isoproposide) of the mixture of TiO₂ solution was varied to 0.05M, 0.1M, 0.2M, 0.3M, and 0.4M. After the deposition process of TiO₂ thin film, the sample was annealed for 20 minutes in the furnace with temperature of 250°C before the Pt deposited as the top electrode of the sample by using sputter coater. For the electrical characterization, current-voltge (I-V) measurement was carried out three times for each sample by considering positive voltage sweep to ensure the stable switching loop obtained. Besides, the physical characteristics of the sample that have been measured were the thickness, surface morphology, oxygen concentration and Raman measurement of the TiO₂ thin film. We found that the precursor molarity does not affect the memristive behaviour however, the sample with less precursor molarity is preferred due to lesser time is required to obtain the stable switching loop.

TABLE OF CONTENTS

TITLE	ERROR! BOOKMARK NOT DEFINED.
SUPERVISOR'S APPROVAL	ERROR! BOOKMARK NOT DEFINED.
CANDIDATE'S DECLARATION	ERROR! BOOKMARK NOT DEFINED.
ACKNOWLEDGEMENT	ERROR! BOOKMARK NOT DEFINED.
ABSTRACT	ERROR! BOOKMARK NOT DEFINED.
TABLE OF CONTENTS	ERROR! BOOKMARK NOT DEFINED.
LIST OF FIGURES	ERROR! BOOKMARK NOT DEFINED.
LIST OF TABLES	ERROR! BOOKMARK NOT DEFINED.
LIST OF ABBREVIATIONS	ERROR! BOOKMARK NOT DEFINED.
CHAPTER 1	ERROR! BOOKMARK NOT DEFINED.
INTRODUCTION	ERROR! BOOKMARK NOT DEFINED.
1.1 BACKGROUND STUDY	Error! Bookmark not defined.
	Error! Bookmark not defined.
	Error! Bookmark not defined.
CHAPTER 2	ERROR! BOOKMARK NOT DEFINED.
LITERATURE REVIEW	ERROR! BOOKMARK NOT DEFINED.
2.1 INTRODUCTION	Error! Bookmark not defined.
2.2 MEMRISTOR	Error! Bookmark not defined.
2.2.1 MEMRISTOR OVERVIEW	Error! Bookmark not defined.
2.2.2 PHYSICAL MEMRISTOR I	DEVICE
2.2.3 MEMRISTIVE BEHAVIOU	JR
2.2.4 MEMRISTOR APPLICATIO	ON9
2.3.1 INTRODUCTION OF TiO ₂ .	
2.3.2 DEPOSITION METHOD	
2.3.2.1 SOL-GEL SPIN OA	TING METHOD 12
	$(\mathbf{A} \mathbf{A} \mathbf{A} \mathbf{A} \mathbf{A} \mathbf{A} \mathbf{A} \mathbf{A} $
2.3.2.2 KADIO-FREQUEN	CY MAGNETRON SPUTTERING 13

CHAPTER 1

INTRODUCTION

1.1 BACKGROUND OF STUDY

The term 'memristor' is basically the simplified term of 'memory resistor' which indicates its function behavior which is, it's able to memorize the recent dynamic resistance even when the power is turned off. Memristor is known as a two-terminal device which the resistance depends on the magnitude and polarity of the voltage applied to it. The main idea of this device is simple which whenever the voltage turned off, this memristor able to remember the most recent resistance until the voltage turned back on. Memristor can be said as a great discovery in the semiconductor industry because it is a new element of analog circuit that works in computer architecture aside of resistor, transistor and capacitor [1].

Basically, there are three basic two terminal circuit elements were defined in terms of a relationship between two of the four fundamental circuit variables, which are the current I, the voltage v, the charge q, and the flux-linkage [2]. Basically, resistor, capacitor and inductor are the only well known fundamentals basic circuit elements which gave us three basic relationships. Those three are resistor relates with voltage and current (dv=R.di), capacitor relates between charge and voltage (dq=C.dv), and inductor relates with flux and current ($d\phi = L.di$). Thus, there are missing link between the charge and magnetic flux [3]. As shown in Figure 1.1, the missing link between charge and magnetic flux were proposed by Dr Leon Chua and called as memristence, ($Mq = d\phi/dq$)[3], [4].